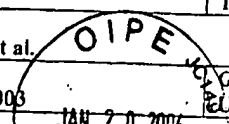


INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)	Docket Number (Optional) TWI-33110	Application Number 10/714,460
	Applicant(s) Rodney Smedt et al.	
	Filing Date November 14, 2003	Group Art Unit Unknown
		

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*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
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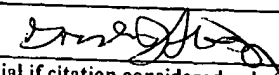
FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
12	AQ	WO 02/25723 A2	03/28/2002	PCT	H01L	21/66	YES NO

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12	AR	H-T. Huang et al., "Scatterometry-Based Overlay Metrology," <i>Metrology, Inspection, and Process Control for Microlithography XVII, Proceedings of SPIE</i> , Vol. 5038 (2003), pp. 126-137.
12	AS	P. Heimann, "The Color-Box alignment vernier: a sensitive lithographic alignment vernier read at low magnification," <i>Optical Engineering</i> , Vol. 29, No. 7, July 1990, pp. 828-836.
12	AT	K.M. Monahan, "Handbook of Critical Dimension Metrology and Process Control," <i>Critical Reviews of Optical Science and Technology, SPIE</i> , Vol. CR52, proceedings of a conference held 28-29 September 1993, pp. cover, 160-188.

Examiner 	Date Considered 3/15/06
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	